

ABSTRACT OF THE DISCLOSURE

Provided is a solid state image pickup element which can exponentially reduce the in-plane photoelectric conversion portion characteristic distribution that is created in forming color filters by a common photolithography technique and which, when color filters are formed by split exposure, can reduce image non-uniformity between exposure regions in a picked-up image, and a method of manufacturing the same. The method includes: applying negative type color resist for forming first color filters onto an entire surface of a given film; forming the first color filters by irradiation of given portions with exposure light and by subsequent development; applying negative type color resist for forming second color filters onto the entire surface of the first color filters while covering the first color filters; and forming the second color filters by irradiating an area smaller than a region that is surrounded by the first color filters with exposure light and by subsequent development. Further, in the solid state image pickup element with color filters of plural colors, one of adjacent color filters is tapered at the edges while the other color filter is reversely tapered at the edges, allowing the adjacent color filters to fit to each other. Furthermore, adjacent color filters are wedged at the edges,

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